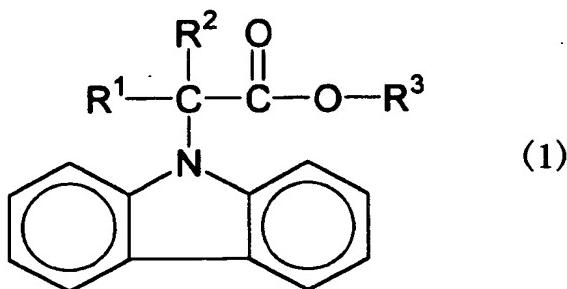


ABSTRACT OF THE DISCLOSURE

A carbazole derivative of the following formula (1),

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wherein R<sup>1</sup> and R<sup>2</sup> individually represent a hydrogen atom or a monovalent organic group, or R<sup>1</sup> and R<sup>2</sup> form, together with the carbon atom to which R<sup>1</sup> and R<sup>2</sup> bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and R<sup>3</sup> represents a hydrogen atom or a monovalent organic group. The carbazole derivative is suitable as an additive for increasing sensitivity of a chemically amplified resist. A chemically amplified radiation-sensitive resin composition, useful as a chemically amplified resist, comprising the carbazole derivative is also disclosed.